

A,
C
V

72. A chamber according to claim 71 wherein the aperture has an aspect ratio selected to reduce deposition of process residue on the radiation transmitting portion.

73. A chamber according to claim 71 comprising means for reducing deposition of process residue on the radiation transmitting portion.

REMARKS

Claims 1-7~~3~~ are presently pending in the case. By this preliminary amendment, claims 1-6, 19, 21, and 27-31 have amended and claims 59-7~~3~~ have been added.

Applicant requests entry of these amendments which are fully supported by the specification and original claims and add no new matter. For example, new claim 59 is supported at least at page 12 lines 16 and 17, page 13 lines 12-14, and page 13 line 32 through page 14 line 2. Additionally, new claim 65 is supported at least by Figure 3a and the specification at page 14 line 29 through page 15 line 7.

Reconsideration of the present case in view of the amendments and remarks herein is requested.

CONCLUSION

The Examiner is respectfully requested to allow the pending claims. Should the Examiner have any questions, the Examiner is requested to call the undersigned representative of the Applicant.

Respectfully submitted,

JANAH & ASSOCIATES
A PROFESSIONAL CORPORATION

Dated: 11/29/2000

By: Ashok Janah
Ashok K. Janah
Reg. No. 37,487

Please direct telephone calls to:

Ashok K. Janah
(415)538-1555

Please continue to send all correspondence to:

Patent Counsel
APPLIED MATERIALS, INC.
P.O. Box 450A
Santa Clara, California 95052